Self-O rganized O rdering of N anostructures P roduced by Ion-Beam Sputtering

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We study the self-organized ordering of nanostructures produced by ion-beam sputtering (IBS) of targets am orphizing under irradiation. By introducing a model akin to models of pattern form ation in aeolian sand dunes, we extend consistently the current continuum theory of erosion by IBS.We obtain new non-linear e ects responsible for the in-plane ordering of the structures, whose strength correlates with the degree of ordering found in experim ents. Our results highlight the importance of redeposition and surface viscous ow to this nanopattern form ation process.

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Perform ance of m any of the (opto)electronic devices currently being designed based on arrays of nanostructures such as quantum dots, requires a high degree of in-plane ordering [1]. Currently, there is a form idable effort to develop experim ental techniques which are able to provide highly ordered nanostructures in a self-organized fashion [2]. These would allow for easy, low-cost and large area fabrication of patterned structures. Am ong these techniques, erosion by ion beam sputtering (IBS) at low energies [3] is a promising candidate [4, 5, 6], leading to production of nanostructures of varying degree of uniform ity and order, onto diverse substrates such as GaSb, InP, and Si. Therefore, detailed know ledge of the basic mechanisms underlying erosion by IBS is crucial to understand and control the associated m anufacturing process. From a fundam ental point of view, the dynam ics of surfaces eroded by IBS exem plies neatly the interplay of uctuations, external driving and dynam ic instabilities, sharing m any features with seem ingly unrelated non-equilibrium systems, such as aeolian sand dunes [7, 8]. Thus, typically surfaces eroded by IBS spontaneously develop submicrometric patterns (dots, pits, ripples) [9] depending on experim ental conditions, may deteriorate and eventually lead to rough interfaces, with uctuations described by the universality classes of kinetic roughening [10].

A successful approach to surface erosion by IBS is provided by continuum evolution equations for the surface height, allowing access to time and length scales typicalof the corresponding pattern form ation process. This approach was pioneered by Bradley and Harper (BH) [11], who, based on Sigm und's linear cascade approxim ation of sputtering in am orphous or polycrystalline targets [3], derived a linear equation that describes satisfactorily the main features of ripple form ation under IBS, such as their alignment with the ion beam as a function of incidence angle. Additional features, such as ripple

stabilization, wavelength dependence with ion energy or ux, or production of dot or hole structures as a function of bom bardm ent conditions, required extensions of BH's approach [12, 13], leading to a non-linear equation of the Kuram oto-Sivashinsky (KS) type. The KS equation provides the continuum description of interfaces appearing in many diverse systems, see in [12], in which a periodic pattern develops, with a preferred wavelength (i.e. the lateral size of the nanostructures), that evolves into a disordered array. Thus, the crucial properties of hom ogeneity and in-plane short-range hexagonal ordering of the nanostructures produced by IBS rem ain to be understood [14]. Recent attem pts have been m ade at extending the KS equation to overcom e such shortcom ings [15, 16], that do not provide de nitive answers, since they either con ict with symmetries of the physical system, or with m athem atical requirem ents for well-posedness [17].

In this Letter, we present a new continuum model of erosion by IBS. It leads to a physically and mathematically well de ned generalization of the KS equation that explains within an uni ed fram ework the varying degree of hom ogeneity and order of the nanostructure arrays produced [4, 5, 6], as a function of experimental parameters. We exploit connections with ripple formation in sand dunes [7], hinted at by A ste and Valbusa [18], overcoming limitations of previous theories [11, 12, 13, 14, 15, 16].

M odel.{ During IBS, the bom barding ions penetrate the target and induce com plex collision cascades in the bulk. In sem iconductor substrates like those studied in [4, 5, 6], these cascades am orphize the near-surface layer. Sputtering events take place when surface atom s receive enough energy and m om entum to break their bonds and leave the target. W e will assume that only a fraction of those atom s are redeposited at the surface. A datom s are m oreover available to relaxation m echanism s such as surface di usion, that can be therm ally activated, or else be induced by the mentioned change in the local viscosity of the material close to the surface [19].

In the spirit of the so-called hydrodynam ic theory of ripples in aeolian sand dunes [7], we de ne two coupled

elds, nam ely, R (x;t) and h (x;t), where x = (x;y). The rst one represents the fraction of surface atom s that are not sputtered away but, rather, rem ain m obile along the target surface. A nalogously, h m easures the height of the surface neglecting the contribution from the fraction of m obile atom s R. T in e evolutions of R and h are coupled through reaction and transport m echanism s [18]. Thus,

$$\begin{aligned}
\theta_t h &= e_x + a_d; \\
\theta_t R &= (1) e_x a_d v r R r J; (2)
\end{aligned}$$

where $_{ex}$ and $_{ad}$ are, respectively, the rates of excavation and addition to the surface, v is the average velocity of mobile atom, and \notin 0 is the fraction of adatom s that detach irreversibly from the surface. Thus, system (1)-(2) does not conserve the amount of material, in marked contrast with typical conditions for aeolian sand dunes [8]. Here, large redeposition of sputtered atoms corresponds to the small limit, while, in the absence of redeposition, = 1. Considering that matter transport along the surface is due to di usion of mobile species, we set r $J = D r^2 R$, where D is the surface di usivity.

In the absence of bom bardment, the concentration of mobile adatoms R changes due to therm al nucleation of adatoms from the \immobile state" h, and subsequent transport along the surface. A ssum ing nucleation events are more likely in surface protrusions, we have ad no er: = ¹ [R R⁰_{eq} (1 +)], analogous of the G ibbs-Thom pson relation, being the mean surface curvature the capillary length, assumed isotropic due to and am orphization by the ion beam . Here is related to the m ean tim e between nucleation events, and R $_{
m eq}^0$ is the mean equilibrium concentration of mobile species for a at surface. In the presence of bom bardment, $ad^{noer:}_{ad}$ has to be generalized, to include the contribution of erosion to surface m obility [19]. If the ions fall onto the target along the x direction, form ing angle with the norm alto the uneroded target, we have, for sm all slopes [20, 21],

$$e_{x} = {}_{0} [1 + {}_{2} (r h)^{2}](1 + {}_{1} r h + {}_{2} r^{2} h)$$

$${}_{0} [{}_{3} (r h)^{2} {}_{4} (0_{x} h) (r^{2} h)] r^{2} h; (3)$$

$$_{ad} = {}_{0} [R \quad R_{eq} (1 \quad {}_{2}r^{2}h)];$$
 (4)

where R_{eq} and $_{i}$ generalize parameters in $_{ad}^{no er:}$ so that $_{0} = {}^{1} + {}_{ex}{}^{1}$, $_{2} = + {}_{ex}$, with $_{ex}{}^{1}$ and $_{ex}$ being analogs of nucleation time and capillary length of erosive origin [7, 19]. Coe cients $_{i}$ 0 in (3) are related to geometric correction factors that take into account the local variation of the ion ux with the surface slopes [20]. E g:, for oblique incidence, $_{1}$; $_{4}$ / sin , and $_{3} = 1=2$. Likewise, coe cient $_{2}$ 0 is related to the local variation of the sputtering yield with the surface

slope [2], assumed to have a local minimum for normal incidence, while 0 measures the e ciency of erosion due to direct in pingement of the ions onto surface atom s (knock-on sputtering) [3, 9]. The positive sign of $_2$ implements the physical instability inherent to Sigmund's theory, by which erosion is more e cient at surface depressions than at surface protrusions [3]. A ctually, the analysis presented below will allow us to relate some of these coe cients with the parameters characterizing Sigmund's distribution of energy deposition.

Surface dynamics. (Our continuum model of IBS, form ed by Eqs. (1)-(2), (3)-(4), provides a way to introduce system atically all relevant physical mechanisms for IBS, diering from that in [18] in a number of features. Rather than considering its full solution, we proceed by deriving an e ective equation for the surface height. As in the experiments of references [4, 5, 6], we consider the case of ions bom barding the target at norm al incidence (= 0), thus $_1 = _4 = jyj = 0$ in (2), (3) [23]. After a transient time of order 0^{-1} , Eqs. (1)-(2) have a planar solution $h_0(t) = 0$ t, $R_0(t) = R_{eq} + (1)$) $_{0}=_{0}$. Perturbing this solution with periodic waves of the form $h_k = \tilde{h}_k \exp(!_k t + i k x)$, and an analogous expression for R_k, ampli cation/decay of such perturbations is characterized by the dispersion relation $!_k$ = $^{1}(D + A)[1 (1)]k^{4}, with =$ k² R_{eq 0 2} $A = (R_{eq 0})$ and $A = 0_2$. If A > 0 in $!_k$, i.e. if sputtering is dom inated by collision cascades rather than knock-on events, as occurs at low to interm ediate energies where Sigm und's theory is applicable, there is a band of unstable modes that grow exponentially fast, with a linear dispersion relation $!_k$ of the expected KS type. At this stage, the surfacem orphology is dom inated by a periodic pattern whose wave-vector maxim izes $!_k$. In-plane isotropy under norm al incidence im plies dependence of $!_k$ on $k = \frac{1}{k}$ jrather than the full wave-vector k, thus the surface power spectral density is, rather, maximum on a ring [6, 14]. Stabilization of this pattern occurs when its am plitude is large enough that non-linear e ects are no longer negligible. C lose to the instability threshold, the rate of erosion is much smaller than the rate of addition to the surface. Hence, parameter above, which is the ratio between these two typical rates, is small. We thus can perform a multiple scale expansion by introducing time scales $T_1 = t$ and $T_2 = {}^2t_r$, and by rescaling length scales as $X = {}^{1=2}x$. To low est non-linear order O () and as seen in the slow variables (X, $T = T_1 + T_2$), surface dynam ics is described by (see [20] for details) [24]

 $\theta_{\rm T} H = r^2 H Kr^4 H + (rH)^2 (rH)^2$

where $H = h_1 + h_2$, and

= A;
$$K = \int_{0}^{1} (D + A) [R_{eq 0 2} A (1)];$$

$$_{1} = _{0} (1=2 _{2});$$
 (6)

$$_{2} = _{0}(1=2 _{2})_{0}^{\perp}[(D + A)(1) R_{eq} _{0}_{2}]$$

Eq. (5) with a noise term, has been already employed in the growth of am orphous thin lm s [25]. In our context, Eq. (5) has some important limits. First, in the absence of ion bom bardment, A = 0 = 0, 0!and $_2$! , and in the original variables (5) reduces to Mullins' equation for therm al surface di usion [26], $\theta_{th} = DR_{eq} r^{4}h$. In the general case, (5)-(6) include contributions to surface di usion that are both therm ally activated, and directly induced by the ion beam as in [19]. Second, the BH lim it corresponds to = 1, i.e., no redeposition. W hile in [18] the BH lim it zeroes out the k^4 contribution to the analog of $!_k$ | thus making the typical length scale of the dot structures rem ain unde ned within linear instability , here Eq. (5) recovers for = 1 the equation obtained within BH's approach to Sigm und's theory [12, 16], including the fact that the coe cients of the two nonlinear terms have the same signs thus making the equation nonlinearly unstable and mathem atically ill-posed [16, 17]. Thus, beyond its experim ental relevance, redeposition is crucial in order to make the theory mathematically sound. On the other hand, the BH lim it allows us to extract the phenom enological dependence of the param eters in our model with characteristics of the collision cascades, such as the ion penetration depth, a, and the longitudinal and lateral widths , and , characterizing the G aussian decay of enery deposition [3]. Thus, for ! 1 we have, in the notation of [12], $_{0} = F$, $_{2} = a^{2} = (2^{2})$, $_{2} = 1$ $^{2}=(2^{2})$ $^{2}=(2^{4}),$ $R_{eq} = 2^{2} = 4$, with F / JE = , where J and E are the

average ion ux and energy, respectively.

Eq. (5) describes the evolution of the erosion process. Initially, dynam ics is controlled by the linear term s, with the same dispersion relation $!_k$ as above, and a periodic pattern develops, with characteristic wavelength given by

$$l_{e} = 2 [2R_{eq} 2(D + A)[1 (1)] = (A)]^{\frac{1}{2}=2};$$
 (7)

providing the typical size of the nanostructures that form. W hen local slopes become large, the nonlinear term s in Eq. (5) control the dynam ics in an opposing way. W hile the 2 term tends to coarsen the nanostructures in am plitude and lateral size, sim ilarly to its rôle in the coarsening of ripples on aeolian sand dunes [7], the nonlinearity 1 tends to disorder the pattern leading to the paradigm atic KS spatiotem poral chaos. Rem arkably, $(r h)^2$ seem s to interrupt the coarsening process induced by $_{2}r^{2}(rh)^{2}$ and the stationary state morphology consists of dom ains of hexagonally ordered nanostructures separated by defects. The density of these is a function of the ratio r = 2 = 1, whose r! 0 lim it in Eq. (5) leaves us with the KS equation. In Fig. 1(a), we plot the stationary-state m orphology obtained by num erical integration of Eq. (5)for a relatively large ratio r = 5 [27]. The high degree of in-plane short range hexagonal ordering is made clear by the height autocorrelation function, shown in the inset of Fig. 1 (a). The time evolution of the dot pattern can be assessed in Fig. 2(a), in which the surface roughness

(m ean height square deviation) W (t) vs t is shown for the same parameters as in Fig. 1 (a). In excellent agreem ent with m easurem ents for nanodots on G aSb [14], the roughness rst increases exponentially during development of the linear instability, attains a maximum value after dots have coarsened to form a densely packed array, and nally relaxes to a sm aller stationary value when defects am ong di erent dot dom ains are annihilated. T im es between linear instability and maximum in the roughness correspond to non-linear coarsening of the dot structures, as seen in the plot of the lateral correlation length $_{\rm c}$ (t), shown on the same panel. We de ne $_{\rm c}$ (t) as the lengthscale provided by the rst secondary maximum of the height autocorrelation. As seen in Fig. 2 (a), $_{\rm c}$ (t) scale is constant during linear instability, grow s as $t^{0:27}$, and saturates at long tim es, in agreem ent with experim ents on InP [5]. This interrupted coarsening process has been also observed on Si [6] (b) and GaSb [14].

Experimental conditions reect in the value of r [28], and can be such that this parameter is substantially sm aller. D ynam ics is then closer to that of the K S equation. The interm ediate coarsening regime narrows, and is followed by kinetic roughening. A surface morphology produced in these conditions [r = 0.5] is shown in Fig. 1 (b), which can be compared with an AFM scan [(d)] of a Sitarget irradiated as in [6]. Again, agreem ent is excellent. Note that the morphology now diers appreciably from that of the KS equation, displayed in Fig. 1 (c). W hile for Eq. (5) a short-range ordered pattern coexists with long-range disorder and roughening, in the pure KS system disorder of the cellular structure is paradigm atic, see the height autocorrelations in Figs. 1 (b); (c). Still, the tim e evolution of the roughness in Fig. 2 (b) (), predicted by Eq. (5) for sm all r values, is sim ilar to that of the KS case, Fig. 2 (b) (+): initial rapid growth is followed by much slower dynamics, and saturation to the stationary state. Such is also the experim ental behavior found for nanostructures produced on Si, see Fig. 3 in [6] (a). Com paring the two plots in Fig. 2 (b), for sm all (non-zero) r values the small-scale nonlinearity 2 is seen to stabilize the linear instability earlier, and leads to sm aller stationary roughness. M oreover, in contrast with Fig. 2 (a), Fig. 2 (b) shows that for small or zero r values, the roughness does not have a local maximum as a function of time.

In sum m ary, we have introduced a continuum m odel for the form ation of nanom etric sized patterns by IBS. The m odel accounts within an uni ed fram ework for experimental features of nanopatterns recently produced on diverse m aterials. Moreover, it leads to an elective interface equation providing new predictions. Thus, considering dependencies [3] on ion energy E of the features of the distribution of deposited energy, a, , , the dot size l_c behaves, in the large redeposition limit . 1, as $l_c = [E + \text{const:}]^{1=2}$. For small E, this in plies l_c is energy independent, while $l_c = E^{1=2}$ for large enough energies. O bservations exist [14, 29] com patible with such energy

dependence, although a system atic study assessing the importance of redeposition would be highly desirable.

From a fundam entalpoint of view, Eq. (5) also leads to new results. Speci cally, this is a height equation with local interactions in which a pattern is stabilized with constant wavelength and am plitude, in contrast with conjectures for 1d system s [30]. A lthough m ore theoretical work is still needed [e.g., regarding the asymptotic properties of Eq. (5)] this suggests that in 2d patterns, coarsening dynam ics is indeed m ore com plex than in 1d [31].

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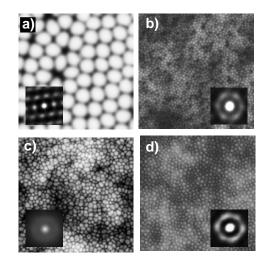


FIG.1: (a) Stationary state morphology from the num erical solution of Eq. (5) with = 2K = 2, $_1 = 0.1$, $_2 = 0.5$, lateral size L = 256. Units are arbitrary. Inset: 2d-autocorrelation, showing high degree of short-range hexagonal order. (b) Sam e as before, for $_1 = 1$, L = 512. (c) sam e as (b) for the KS equation, $_2 = 0$. (d) 3 3 m 2 AFM scan of a Sitarget irradiated as in Ref. [6] for 4 h.

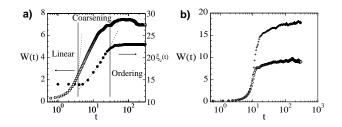


FIG.2: (a) W (t) and $_{c}$ (t) from Eq.(5) for Fig.1(a). D otted line in the linear (coarsening) region grows as an exponential (as $t^{0.27}$). (b) W (t) for Fig.1(b) (), and Fig.1(c) (+).